

Title (en)

POLYMERIZABLE COMPOSITION, POLYMER, RESIST, AND LITHOGRAPHY METHODS

Title (de)

POLYMERISIERBARE ZUSAMMENSETZUNG, POLYMER, RESIST UND LITHOGRAPHIEVERFAHREN

Title (fr)

COMPOSITION POLYMERISABLE, POLYMER, RESERVE ET PROCEDE DE LITHOGRAPHIE

Publication

EP 1523698 A1 20050420 (DE)

Application

EP 03787737 A 20030721

Priority

- DE 0302502 W 20030721
- DE 10233849 A 20020722

Abstract (en)

[origin: DE10233849A1] A polymerizable composition (I) for the production of a resist (II) contains at least one unsaturated polymerizable monomer having at least one silicon atom and at least one carbonyl group. Independent claims are included for: (1) a polymer (III) prepared by polymerization of the composition (I); (2) a resist (II) comprising 2-30% polymer (III), 70-98% solvent and 0.1 -10% of a photoacid initiator; (3) a lithographic process for the production of a structure on a substrate, preferably a lithographic mask for the production of semiconductor components by use of a resist (II).

IPC 1-7

G03F 7/075; C08F 30/08; C08F 230/08; G03F 7/039

IPC 8 full level

C08F 30/08 (2006.01); **G03F 7/039** (2006.01); **G03F 7/075** (2006.01)

CPC (source: EP KR US)

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Citation (search report)

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